

Supplementary Materials: Deposition of $\text{SiO}_x\text{C}_y\text{H}_z$ Protective Coatings on Polymer Substrates in an Industrial-Scale PECVD Reactor

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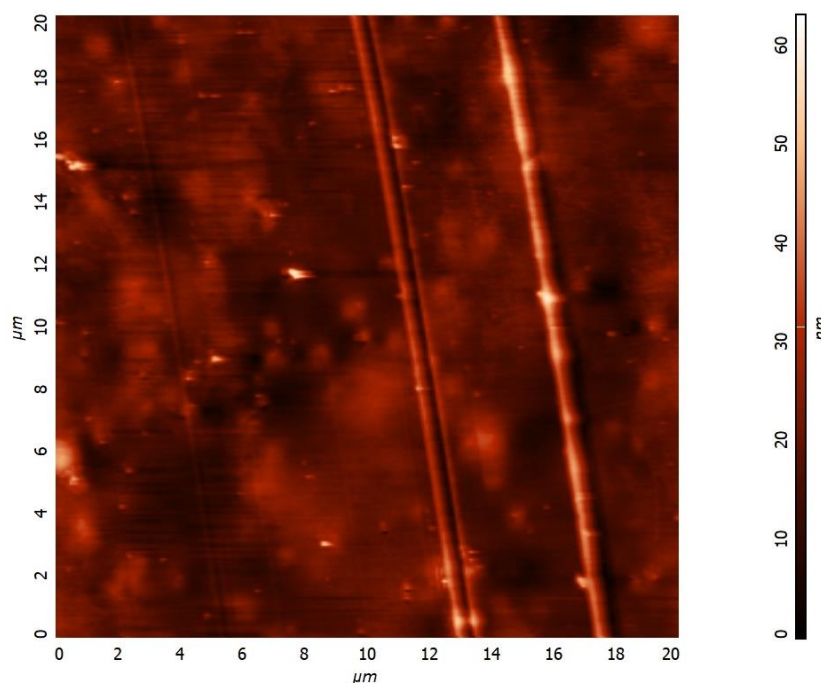


Figure S1. One of the AFM images of the untreated sample. Measurements with AFM were performed on 3 samples at different places. The average roughness was around $S_a = 5$ nm ($S_q = 6.5$ nm).

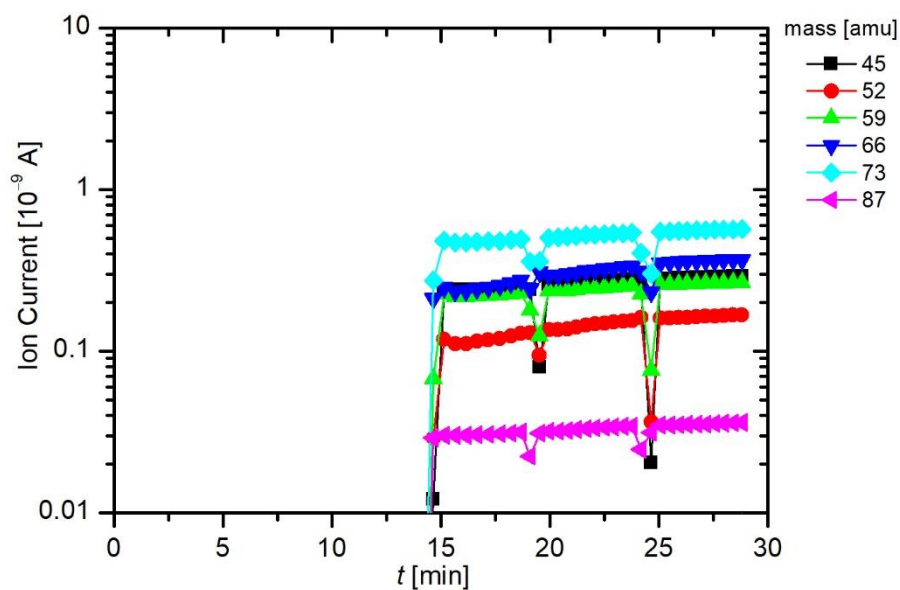


Figure S2. Mass spectrometry of gaseous molecules of higher masses during all phases of the production process.



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